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|---|--------|--|----------|------------|
| - | 20394 | gate adj2 insulating | USPAT; | 14:51 |
| - | 19039 | thin adj2 oxide) (ultrathin adj2 oxide | EPO; JPO | 2002/10/29 |
| - | 1124 | (gate adj2 insulating) and (thin adj2 oxide) (ultrathin adj2 oxide) and polysilicon | USPAT; | 16:07 |
| - | 188199 | hydrogen and oxygen | USPAT; | 2002/10/29 |
| - | 227 | (hydrogen and oxygen) and ((gate adj2 insulating) and (thin adj2 oxide) (ultrathin adj2 oxide) and polysilicon) | EPO; JPO | 16:08 |
| - | 101606 | hydrogen same oxygen | USPAT; | 2002/10/29 |
| - | 122 | (hydrogen same oxygen) and ((gate adj2 insulating) and (thin adj2 oxide) (ultrathin adj2 oxide) and polysilicon) | EPO; JPO | 16:09 |
| - | 80371 | hydrogen with oxygen | USPAT; | 2002/10/29 |
| - | 88 | (hydrogen with oxygen) and ((gate adj2 insulating) and (thin adj2 oxide) (ultrathin adj2 oxide) and polysilicon) | EPO; JPO | 16:14 |
| - | 1 | (hydrogen with oxygen) and ((gate adj2 insulating) and (thin adj2 oxide) (ultrathin adj2 oxide) and polysilicon) | USPAT; | 2002/10/30 |
| - | 9 | and ISSG | EPO; JPO | 10:11 |
| - | 8 | ISSG "in situ steam generation" | USPAT; | 2002/10/30 |
| - | 5957 | (ISSG "in situ steam generation") and gate | EPO; JPO | 10:31 |
| - | 54 | EEPROM and oxide | USPAT; | 2002/10/30 |
| - | 280 | (EEPROM and oxide) and SONOS | EPO; JPO | 10:31 |
| - | 0 | EEPROM and ("form oxide") | USPAT; | 2003/04/27 |
| - | 1 | EEPROM and ("form oxide") near (oxygen adj3 hydrogen) | EPO; JPO | 14:47 |
| - | 184 | ("form oxide") near (oxygen adj3 hydrogen) | USPAT; | 2003/04/27 |
| - | 16 | ("wet oxidation" or "steam oxidation") and EEPROM | EPO; JPO | 14:52 |
| - | | (("wet oxidation" or "steam oxidation") and EEPROM) and (ultrathin "ultra thin" "ultra-thin") | USPAT; | 2003/04/27 |
| | | | EPO; JPO | 14:53 |
| | | | USPAT; | 2003/04/27 |
| | | | EPO; JPO | 15:00 |
| | | | USPAT; | 2003/04/27 |
| | | | EPO; JPO | 15:01 |